

Title (en)

HIGH-VOLTAGE INSULATOR ARRANGEMENT, AND ION ACCELERATOR ARRANGEMENT COMPRISING SUCH A HIGH-VOLTAGE INSULATOR ARRANGEMENT

Title (de)

HOCHSPANNUNGSISOLATORANORDNUNG UND IONENBESCHLEUNIGERANORDNUNG MIT EINER SOLCHEN HOCHSPANNUNGSISOLATORANORDNUNG

Title (fr)

DISPOSITIF D'ISOLATION HAUTE TENSION ET DISPOSITIF ACCÉLÉRATEUR D'IONS COMPRENANT UN TEL DISPOSITIF D'ISOLATION HAUTE TENSION

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Application

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Abstract (en)

[origin: WO2009037195A1] The invention relates to an ion accelerator arrangement comprising an electrostatic acceleration field between a cathode to which a frame potential is applied and an anode to which a high-voltage potential is applied. Said ion accelerator arrangement further comprises a gas supply system into which a gas-permeable, open porous insulator member is introduced. Also described is a high-voltage insulator arrangement that comprises such an insulator member and is suitable, inter alia, for such an ion accelerator arrangement and for the corona-resistant insulation of other components to which a high voltage is applied.

IPC 8 full level

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